

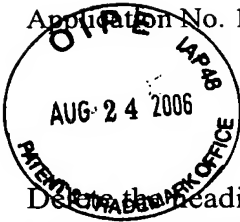
Application No. 10/530,026

Reply to Office Action

AMENDMENTS TO THE TITLE

Replace the title with:

Method and Apparatus for Producing Thin-Film Polycrystalline Silicon Film and
Method of Manufacturing Semiconductor and Production Device and Thin-Film
Transistor



AMENDMENTS TO THE SPECIFICATION

Delete the heading beginning at page 6, line 17:

~~Description of the Reference Characters~~

Delete the paragraph beginning at page 6, line 18:

~~1 pulse laser beam source, 2 first pulse laser beam, 6 second pulse laser beam, 8 focusing and irradiation optical system, 9 object to be irradiated, 10 non-linear optical element, 11 focusing lens, 12 bend mirror, 13 beam adjusting optical system, 14 stage, 21 focusing lens (for focusing a beam into a line shape), 22 first pulse laser beam (focused into a line shape), 23 second pulse laser beam (focused into a line shape), 24 profile (of the focused first pulse laser beam), 24n profile (of a newly applied first pulse laser beam), 25 profile (of the focused second pulse laser beam), 26 melted portion, 27 longitudinal direction (of the beam focused into the line shape), 29 crystal grain, 31, 38 laterally growing crystal, 32 arrow (indicating a direction in which the crystal grows), 34 arrow (indicating a direction in which a region irradiated with the first pulse laser beam relatively scans) 35 region (irradiated with the first pulse laser beam), 36 region (irradiated with the second pulse laser beam), 37 amorphous portion, 51 pulse laser beam source (generating the second pulse laser beam), 52 dichroic mirror, 53 optical axis (of the first pulse laser beam), 54 optical axis (of the second pulse laser beam), 71 arrow (indicating a direction in which the object moves), 80 prism, 101 internal wavelength conversion type solid state laser device, 115 solid state laser medium, 116 semiconductor laser element, 117 fundamental wave laser beam, 118 Q switch, 119 second harmonic generating non-linear optical element, 120 first end mirror, 121 second end mirror, 122 second harmonic extraction mirror, 123 bend mirror, 124 case, 125 beam extraction window, 201 insulating substrate, 202 base film, 203 amorphous silicon film, 204 arrow (indicating laser irradiation), 206 (patterned) polycrystalline silicon film, 207 gate insulating film, 208 gate electrode, 209 source electrode, 210 drain electrode, 211 interlayer insulating film.~~